

ACT[®] CMI-S

ORGANIC ETCH RESIDUE AND POSITIVE PHOTORESIST STRIPPER

ACT CMI-S is a corrosion inhibited water-soluble solution which effectively removes hard-processed positive resist and organic etch residue from corrosion-sensitive metal alloy substrates.

BENEFITS

- Low etch rates on aluminum and aluminum alloys
- Completely water-soluble
- Operating temperature of 60°C to 75°C
- Compatible with wet bench and spray tool processes

TYPICAL PHYSICAL PROPERTIES

Specific Gravity:	0.940
Boiling Point:	164°C
Freezing Point:	<-15°C
Flash Point (Open cup):	78°C
Flash Point (Closed cup):	63°C
Viscosity @25°C:	1.12 cSt
pH (5% solution):	10.26

MATERIAL COMPATIBILITY

ACT CMI-S is compatible with the following materials used in the semiconductor industry*:

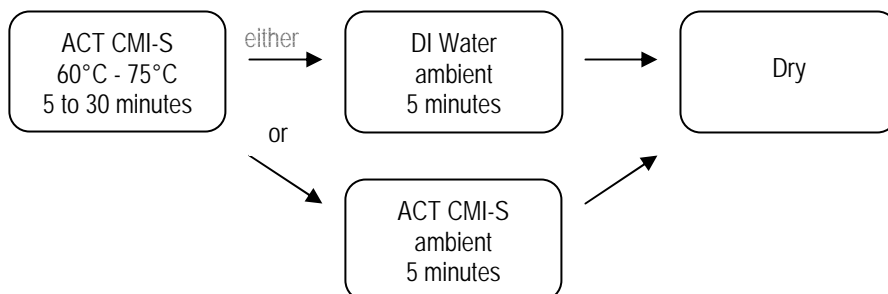
Test Conditions: 10 days at 22°C

Chemraz¹ 570
Halar 901
Kalrez² 6375
PFA
POE
Polyethylene, Cross Linked
Polyethylene, High Density
Polyethylene, UHMW
Polypropylene
Stainless Steel 316L
Stainless Steel 316LEP
Teflon³ PTFE

Test Conditions: 10 days at 80°C

PFA
Polyethylene, High Density
Stainless Steel 316LEP
Teflon³ PTFE

INSTRUCTIONS FOR USE



ACT[®] CMI-S

ETCH RATES

Etch Rates (Å/min)**								
Temp.	Al	Cu	Ti	Ta	TaN	W	TiN	TiW
75°C	1	18	<1	<1	<1	3	<1	1

**Thickness measurements were performed using a CDE ResMap 273 four-point probe for metal films and the Nanospec⁴ AFT model 010-0180 film thickness measurement system for oxide films.

STORAGE, HANDLING, AND PROTECTIVE CLOTHING

Contact the Air Products Technical Center at 1-800-752-1597 or gastech@airproducts.com for a MSDS.

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